

AMENDMENTS TO THE CLAIMS

The following listing of claims will replace all prior versions and listings of claims in the application:

Claim 1 (currently amended): A linearity measuring apparatus for a wafer orientation flat, comprising:

a base in which ~~one, two, or more~~ a plurality of straight tracks are formed in a first direction;

a platform which is configured so as to be movable in said first direction by being engaged with said plurality of straight [[track]] tracks via engagement means, and is further provided with a top surface formed so as to be flat to mount a wafer having an orientation flat;

a block which is installed on said base with a predetermined first clearance L being provided with the between said block and a nearest one of said plurality of straight [[track]] tracks in a second direction perpendicular to said first direction, and has a flat face against which the orientation flat of said wafer mounted on said platform abuts and which is parallel with said first direction;

wafer fixing means provided in said platform to fix said wafer in a state in which said wafer is mounted on said platform; and

a measurement device which is installed on said base with a predetermined second clearance M being provided with said block in said first direction, and has a probe that is opposed to said plurality of straight tracks [[track]] and is capable of being displaced in said second direction, wherein

when a clearance between [[the]] a tip end of said probe and the nearest one of said

plurality of straight tracks [[track]] is taken as N, the following equation (1) is satisfied:

$$0 \mu\text{m} < L-N \leq 100 \mu\text{m}, [[\dots\dots\dots (1)]]$$

Claim 2 (currently amended): The linearity measuring apparatus according to claim 1, wherein said wafer fixing means has a suction port formed in said platform to attract and fix said wafer, a suction passage communicating with said suction port, and a switching valve provided in said suction passage to switch said suction port to a negative pressure or [[the]] atmospheric pressure.

Claim 3 (currently amended): The linearity measuring apparatus according to claim 1, wherein release means for moving said block in said second direction in which said block goes apart from said plurality of straight tracks [[track]] is installed on said base.

Claim 4 (original): The linearity measuring apparatus according to claim 1, wherein deflection data displayed on said measurement device can be outputted as an electronic signal.

Claim 5 (original): The linearity measuring apparatus according to claim 1, wherein said apparatus can be applied to a wafer having a diameter in the range of 50 to 300 mm.